

L Number	Hits	Search Text	DB	Time stamp
1	32201	((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) same (mesh or screen or filter) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/08 15:25
2	16606	((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) same (mesh or screen) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/08 16:22
3	7584	((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) with (mesh or screen) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/08 16:28
4	64	((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) with (mesh or screen) with (teflon or polytetrafluoroethylene)) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/08 16:49
5	146	((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) same (mesh or screen) with (teflon or polytetrafluoroethylene)) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/08 16:51
6	82	((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) same (mesh or screen) with (teflon or polytetrafluoroethylene)) and (substrate or wafer)) not (((showerhead or (shower adj head)) or distrib\$5 or dispers\$4) with (mesh or screen) with (teflon or polytetrafluoroethylene)) and (substrate or wafer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/08 16:51
-	4302	(118/52,56,58,62,63).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2002/09/30 11:29
-	17	((118/52,56,58,62,63).CCLS.) and (showerhead or (shower adj head) or ((dispers\$3 or distribut\$3) adj plate)) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/04 15:41
-	17	((118/52,56,58,62,63).CCLS.) and (showerhead or (shower adj head) or ((dispers\$3 or distribut\$3) adj plate)) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2002/09/30 11:45

-	247	((118/52,56,58,62,63).CCLS.) and (mesh or screen or filter) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/04 15:39
-	48	((118/52,56,58,62,63).CCLS.) and ((mesh or screen or filter) with (gas or vapor)) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2002/09/30 11:48
-	46	((118/52,56,58,62,63).CCLS.) and ((mesh or screen or filter) with (gas or vapor)) and (substrate or wafer)) not ((118/52,56,58,62,63).CCLS.) and (showerhead or (shower adj head) or ((dispers\$3 or distribut\$3) adj plate)) and (substrate or wafer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2002/09/30 11:48
-	7	((118/52,56,58,62,63).CCLS.) and (mesh or screen or filter) and ((substrate or wafer) same chuck) and (inlet same source)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2002/09/30 12:00
-	2	((118/52,56,58,62,63).CCLS.) and (mesh or screen or filter) and ((substrate or wafer) same chuck) and (inlet same source)) not ((118/52,56,58,62,63).CCLS.) and ((mesh or screen or filter) with (gas or vapor)) and (substrate or wafer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2002/09/30 12:01
-	2	("6287987").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2002/09/30 12:02
-	18	((118/52,56,58,62,63).CCLS.) and (showerhead or (shower adj head) or ((dispers\$3 or distribut\$3) adj plate)) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/04 15:40
-	260	((118/52,56,58,62,63).CCLS.) and (mesh or screen or filter) and (substrate or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/08 15:15
-	270	((118/52,56,58,62,63).CCLS.) and (showerhead or (shower adj head) or ((dispers\$3 or distribut\$3) adj plate)) and (substrate or wafer)) or ((118/52,56,58,62,63).CCLS.) and (mesh or screen or filter) and (substrate or wafer))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/04 15:41

-	14	(((118/52,56,58,62,63).CCLS.) and (showerhead or (shower adj head) or ((dispers\$3 or distribut\$3) adj plate)) and (substrate or wafer)) or (((118/52,56,58,62,63).CCLS.) and (mesh or screen or filter) and (substrate or wafer))) and @pd>=20020930	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB; USOCR	2003/03/04 18:36
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